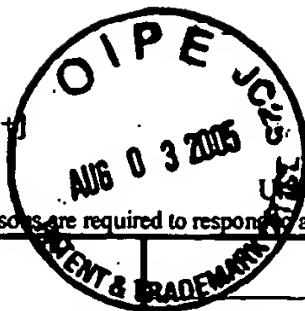


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Substitute for form 1449A/PTO				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)				Application Number	09/836,449
				Filing Date	April 17, 2001
				First Named Inventor	Stephen J. FONASH
				Group Art Unit	2812
				Examiner Name	Richard A. Booth
Sheet	1	of	1	Attorney Docket Number	201009-007000

U.S. PATENT DOCUMENTS						
Examiner Initials [*]	Cite No. ¹	U.S. Patent Document		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number	Kind Code ² (if known)			
JS		5,594,171		Ishida et al.	January 14, 1997	

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JS			EP 0 895 276 A1		Bruno Murari	March 2, 1999	

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JS		Supplementary Partial European Search Report	
		FURUKAWA, et al. Nickel Surface Micromachining, Sixth International Symposium on Micro Machine and Human Science, 1995, pp. 161-165, IEEE.	
JS		WALTER LANG, Silicon Microstructuring Technology, Materials Science and Engineering, Reports: A Review Journal R17 (1996), pp. 1-55.	

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1/25		US-6,486,041	11/26/02	Henley, et al.	
		US-6,399,177	06/04/02	Fonash, et al.	
		US-6,372,608	04/16/02	Shimoda, et al.	
		US-6,225,192	05/01/01	Aspar, et al.	
		US-6,214,701	04/10/2000	Matsushita, et al.	
		US-6,158,824	12/12/00	Yonemura, et al.	
		US-5,854,123	12/29/98	Sato, et al.	
		US-5,641,709	06/24/97	Lee	
		US-5,690,753	11/25/97	Kawauchi, et al.	
		US-5,690,763	11/25/97	Ashmead, et al.	
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		US-5,866,204	02/02/99	Robbie, et al.	
		US-6,555,443	04/29/03	Artmann, et al.	
		US-5,242,863	09/07/93	Xiang-Zheng, et al.	
		US-6,774,010	08/10/04	Chu, et al.	
		US-5,594,171	01/14/97	Ishida, et al.	
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		US-6,372,608	04/16/02	Shimoda, et al.	
		US-6,486,041 B2	11/26/02	Henley, et al.	
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		US-6,449,079 B1	09/10/02	Hermann	
		US-6,555,443	04/29/03	Artman, et al.	
		US-6,774,010	08/10/04	Chu, et al.	
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		US-2002/0068419	06/06/02	Sakaguchi, et al.	
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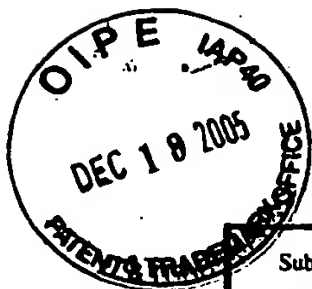
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		DE 198 41 430		05/25/00			
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Richard A. Booth

07/23/06



Substitute for form 1449A/PTO

**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

(use as many sheets as necessary)

Complete if Known

Application Number	09/836,449
Filing Date	April 17, 2001
First Named Inventor	Stephen J. FONASH
Art Unit	2812
Examiner Name	Richard A. BOOTH
Attorney Docket Number	201009-007000

Sheet	2	of	4
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/ /		EP	895 276 A1	02/99			
		EP	0 297 258	04/08/92			
		WO	00/74932 A1	12-14-00			
		WO	01/80286 A2	10-25-01			✓
		WO	03/050854 A2	06/19/03			
		WO	99/27325 A2	06/99			

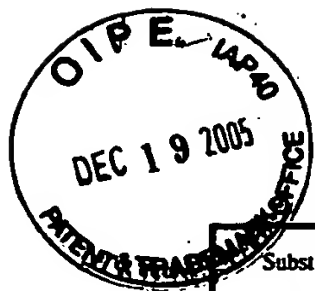
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/ /		LEE, et al., A novel fabrication technology for Si TFTs on flexible substrates, ECS Extended Abstract No. 791, Electrochemical Society meeting, October 2000.	
		WAGNER, et al., Flexible display enabling technology, Cockpit Displays VIII: Displays for Defense Applications, Proc. SPIE Vol. 4362, p. 226-244, September, 2001.	
		STURM, et al., Enabling Technologies for Plastic Displays, Cockpit Displays IX: Displays for Defense Applications, Proc. SPIE Vol. 4712, p. 222-236, August 2002.	
		LI, et al., Transfer approach toward fabricating poly-Si TFTs on plastic substrates ECS Extended Abstracts No. 647, Electrochemical Society meeting, Oct., 2002.	
		LEE, et al., High Performance Poly-Si TFTs on Plastic Substrates Using a Nano- Structured Separation Layer Approach, IEEE Electron Device Letters, Vol. 24, No. 1, January 2003.	
		KALKAN, et al., Nanocrystalline Si Thin Films With Arrayed Void-Column Network Deposited By High Density Plasma, Journal Of Applied Physics, Vol. 88, No. 1, July 1, 2000, PP. 555-561.	
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/ /		CHOU, et al., Nanoimprint lithography, J. Vac. Sci., Tech. B, 1996, 14(6), 4129-4133.	

Examiner Signature	<i>Richard A. Booth</i>	Date Considered	07/23/06
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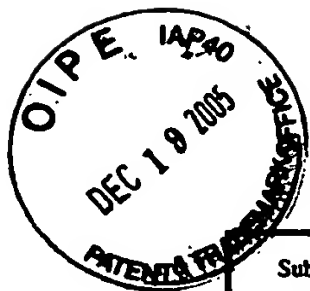
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1/12		COLBURN, et al., Step and Flash Imprint Lithograph, Solid State Technology, July 2001.	
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Examiner Signature	<i>Richard A. Booth</i>	Date Considered	07/23/06
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NA		H. G. CRAIGHEAD, Issues In Nanotechnology Review - Nanoelectromechanical Systems, Science Mag. November 24, 2000, Vol. 290, 532-1535.	
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